

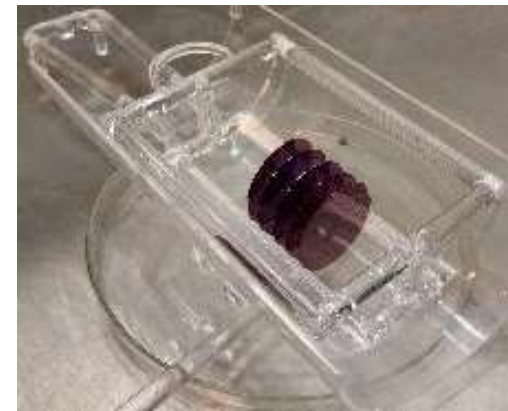
Thermal Anneal/FGA (Ultra Clean Samples)

▪ *N₂ Anneal:*

- Samples : up to 4" wafers
- Gases : N₂
- Temperatures : 300°C to 1050°C

▪ *FGA Anneal:*

- Samples : up to 4" wafers
- Gases : H₂:Ar (5%:95%) mixture
- Temperatures : 300°C and 800°C



Wet Oxidized wafers